Supporting Information

A Single-Layer of MoS_2 Activates Gold for Room Temperature CO Oxidation on an Inert Silica Substrate

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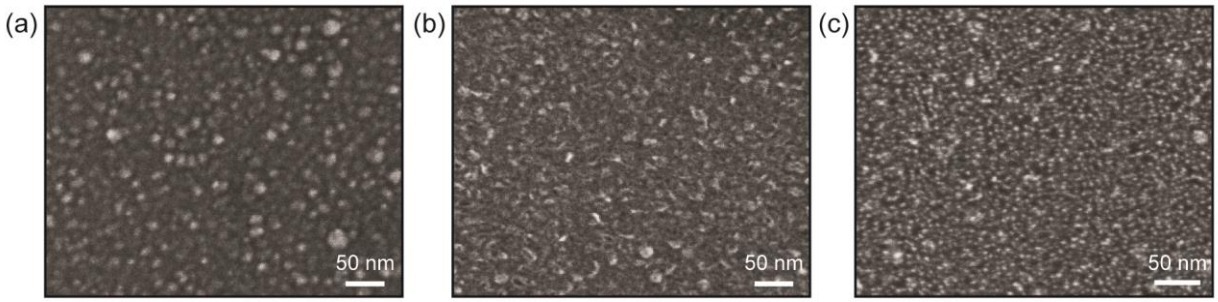

Fig. S1 (a) SEM imaging of a silicon wafer after 30 nm SiO_2 deposition via PECVD, (b) after MoS_2 deposition, and (c) after 3 Å Au deposition.

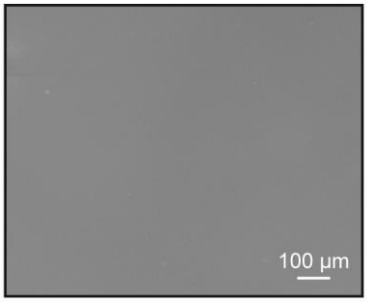

Fig. S2 Low magnification SEM image of single-layer MoS_2 on the substrate.

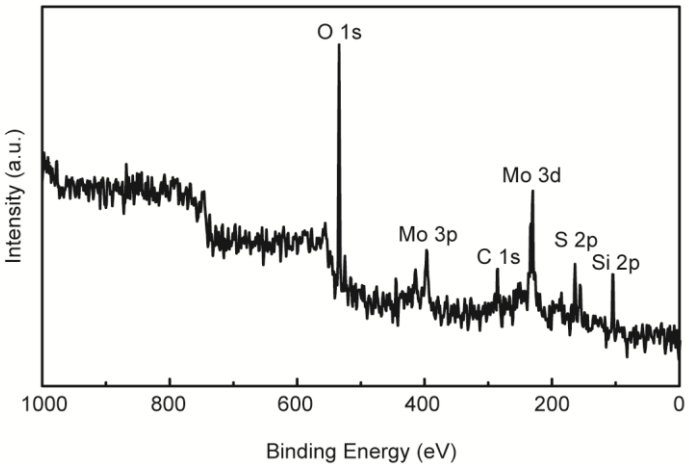

Fig. S3 XPS survey scan of single-layer MoS_2 on the substrate.

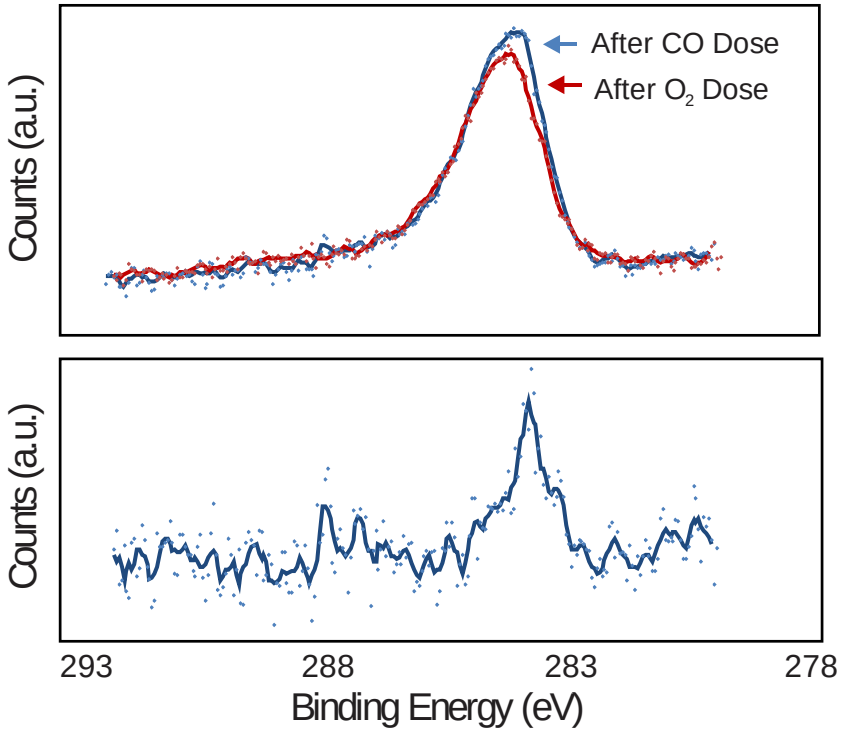

Fig. S4 Comparison of XPS carbon 1s signature after CO dosing and subsequent exposure to oxygen at room temperature. The bottom panel shows the difference spectrum. Data points are indicated; the solid lines are 5-point running averages.